

Appl. No.: 10/803,393

Amdt. dated 02/02/2006

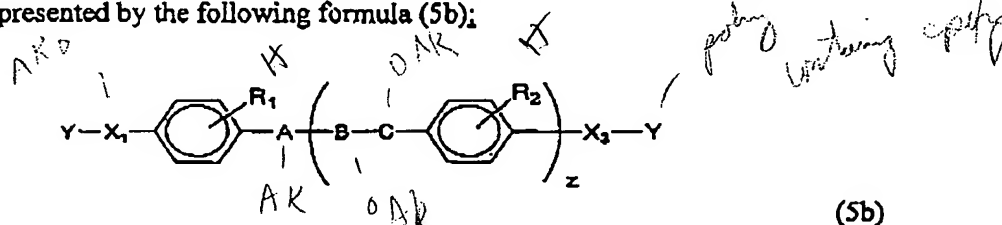
Reply to Office Action of October 3, 2005

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 15 is used as said photosensitive composition for optical waveguides.

Claims 18-20 (Cancelled)

21. (Previously Presented) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being an oligomer represented by the following formula (5b):



wherein R_1 and R_2 may be the same as or different from each other, and denote hydrogen, halogen, an alkyl group, an alkoxy group or a trifluoromethyl group; X_1 and X_3 may be the same as or different from each other, and denote a connection group including at least one selected from the group consisting of an alkyleneoxy and oxyalkylene group; Y denotes a polymerization activating group containing an epoxy group and A denotes a connection group selected from a linear or branched alkylene group; B denotes a connection group selected from a substituted or an unsubstituted oxyalkylene; C denotes a connection group selected from oxyalkylene, said oxyalkylene of B and said alkyleneoxy C including at least one OH group; and $z = 1$ or 2 .

22. (Currently amended) ~~A~~ ~~[[The]]~~ photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer represented by the following formula claimed in claim 15, wherein said organic oligomer is selected from the compound having the following formula (19):